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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Yu Min Lin, et al.	§	Docket No.:	24061.69
		§		(TSMC2002-1055/1057)
Serial No.:	10/763,643	§		
		§	Examiner:	Asok K. Sarkar
Filed:	January 23, 2004	§		
		§	Art Unit:	2891
For:	System and Method for	§		
	Integration of HfO ² and	§	Conf. No.:	7730
	RTCVD Ply-Silicon	§		

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
Mail Stop: Amendment
PO Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The present paper is being submitted in response to the Restriction Requirement Office Action dated May 23, 2005 in the above-identified application.

Election of Claims begins on page 2 of this paper.

Amendments to the Claims are reflected in the Listing of Claims which begins on page 3 of this paper.

Remarks begin on page 12 of this paper.

I. Election

In the Office Action mailed May 23, 2005, the Examiner alleges that the application contains claims directed to two inventions and, thus, required restriction of either:

Claims 1-55 (Group I), drawn to a method for forming a device; or

Claims 56-60 (Group II), drawn to a device.

In response, Applicants hereby elect Group I, corresponding to claims 1-55. Applicants' election is made with traverse on the grounds that the embodiments delineated by the Examiner are not patentably distinct and therefore constitute a single invention concept.